



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of

Genji Imai et al.

Application No.: 10/627,891

Filed: July 28, 2003

For: POSITIVE SENSITIVE RESIN  
COMPOSITION AND A PROCESS  
FOR FORMING A RESIST  
PATTERN THEREWITH

) **MAIL STOP AF**

) Group Art Unit: 1752

) Examiner: CYNTHIA HAMILTON

) Confirmation No.: 3805

**REPLY AND AMENDMENTS PURSUANT TO 37 C.F.R. §1.116**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Office Action [Final Rejection] dated February 22, 2005,  
please amend the above-identified patent application as follows:

5/10/05/4  
Amendment -  
this  
Enter